

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|-------|--|---|------------------|---------|---------------------|
| L1 | 14261 | etch\$3 near3 (sacrificial dielectric) and (gate with (sacrificial dielectric)) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2008/10/09 13:46 |
| L2 | 36796 | ((substrate or wafer) with (dielectric or oxide or insulat \$3 or ILD IMD) with (gate polysilicon electrode) with (sacrificial dielectric or oxide or insulat \$3 or ILD IMD)) and (remov\$3 etch \$3) near1 (sacrificial dielectric or oxide or insulat \$3 or ILD IMD) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2008/10/09 13:46 |
| L3 | 7039 | 1 and 2 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2008/10/09 13:47 |

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